

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	0	(first adj dielectric adj layer) with (first adj depositon adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 06:42
L2	2	(first adj dielectric adj layer) with (first adj deposition adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 06:48
L3	16	hill-chris-w.inv.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 06:43
L4	2	(first adj dielectric adj film) with (first adj deposition adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 06:48
L5	2	(first adj dielectric adj layer) same (first adj deposition adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 06:48
L6	2	(first adj dielectric adj film) same (first adj deposition adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 06:49
L7	4	(first adj dielectric adj film) near (deposition adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 06:51
L8	5	(first adj dielectric adj layer) near (deposition adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 06:52
L9	11	(first adj dielectric) near (deposition adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 06:53
L10	31	(first adj dielectric) with (deposition adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 06:57

L11	56	(first adj dielectric) same (deposition adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 07:01
L12	0	(plurality adj dielectric adj layers) near (deposition adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 07:02
L13	0	(plurality adj dielectric adj layers) with (deposition adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 07:02
L14	0	(plurality adj dielectric adj layers) same (deposition adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 07:03
L15	11	(plurality adj dielectric adj layers) and (deposition adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 07:03
L16	0	(plurality adj dielectric adj films) near (deposition adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 07:04
L17	0	(plurality adj dielectric adj films) with (deposition adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 07:04
L18	3	(plurality adj dielectric adj films) and (deposition adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 07:04
L19	0	(plurality adj dielectric) near (deposition adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 07:04
L20	0	(plurality adj dielectric) with (deposition adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 07:04

L21	1	(plurality adj dielectric) same (deposition adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 07:05
L22	38	(plurality adj dielectric) and (deposition adj rate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 08:28
L23	86	(dielectric) and (different adj deposition adj rates)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 09:20
L24	496	438/981.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 09:23
L25	1154	438/778.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 09:24
L26	1556	438/780.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 09:25
L27	569	438/784.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 09:25
L28	2854	438/763.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 09:25
S1	2	"6319848".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/27 06:42
S2	2	"5104482".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/25 19:25